

DuPont™ PlasmaSolv® EKC270™

Post-Etch Residue Remover

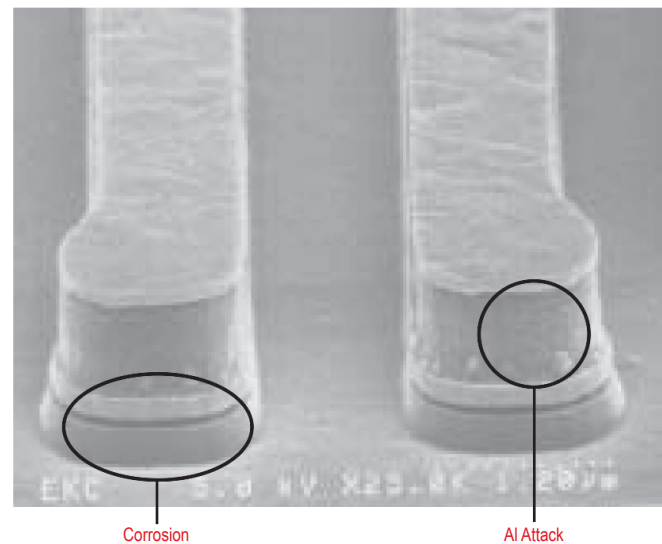
DuPont™ PlasmaSolv® EKC270™ post-etch residue remover is made with DuPont™ HDA® hydroxylamine technology for enhanced performance.

Benefits

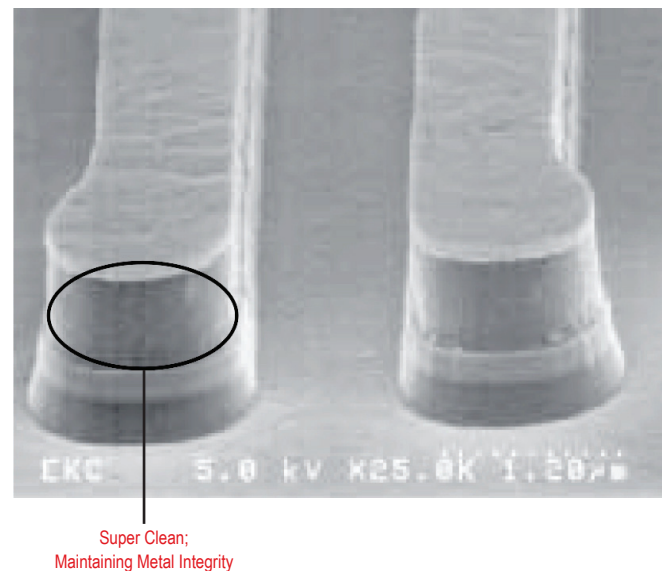
- Formulated for optimum metal stack integrity
- “Improved” wide window process capability
- Enhanced post etch residue removal
- Patented and patent pending improved reduction chemistry
- Ultra Large Scale Integration (ULSI) grade specifications for advanced wafer cleaning
- Low evaporation rate at operating temperature

Figure 1. DuPont™ PlasmaSolv® EKC270™ demonstrates superior performance, even under aggressive processing conditions (75 °C for 50 min)

1a. Conventional Remover



1b. DuPont™ EKC270™





ekctech.dupont.com

For more information on DuPont™ PlasmaSolv® EKC270™ or other DuPont products, please visit our website.

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CAUTION: Do not use in medical applications involving permanent implantation in the human body. For other medical applications, see "DuPont Medical Caution Statement," H-50102-5 and "DuPont Policy Regarding Medical Applications" H-50103-5.

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